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(54) **INDUCTIVELY-DRIVEN PLASMA LIGHT SOURCE**

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(52) **U.S. Cl.** ..... **313/31; 315/248; 313/279**

(58) **Field of Classification Search** ..... **378/119; 313/31; 315/248**  
See application file for complete search history.

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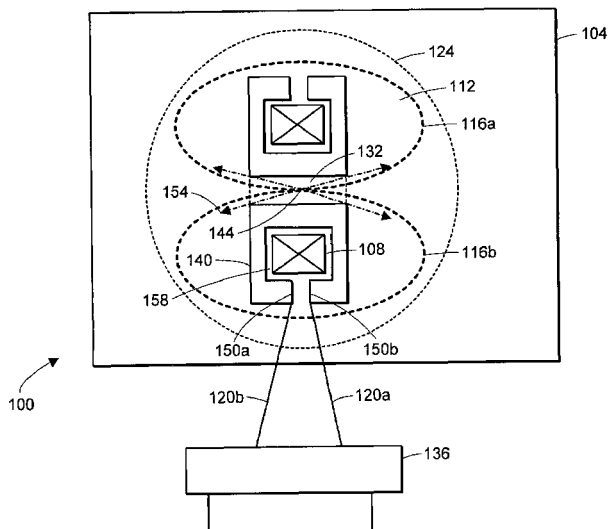
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(57) **ABSTRACT**

An apparatus for producing light includes a chamber that has a plasma discharge region and that contains an ionizable medium. The apparatus also includes a magnetic core that surrounds a portion of the plasma discharge region. The apparatus also includes a pulse power system for providing at least one pulse of energy to the magnetic core for delivering power to a plasma formed in the plasma discharge region. The plasma has a localized high intensity zone.

**51 Claims, 8 Drawing Sheets**



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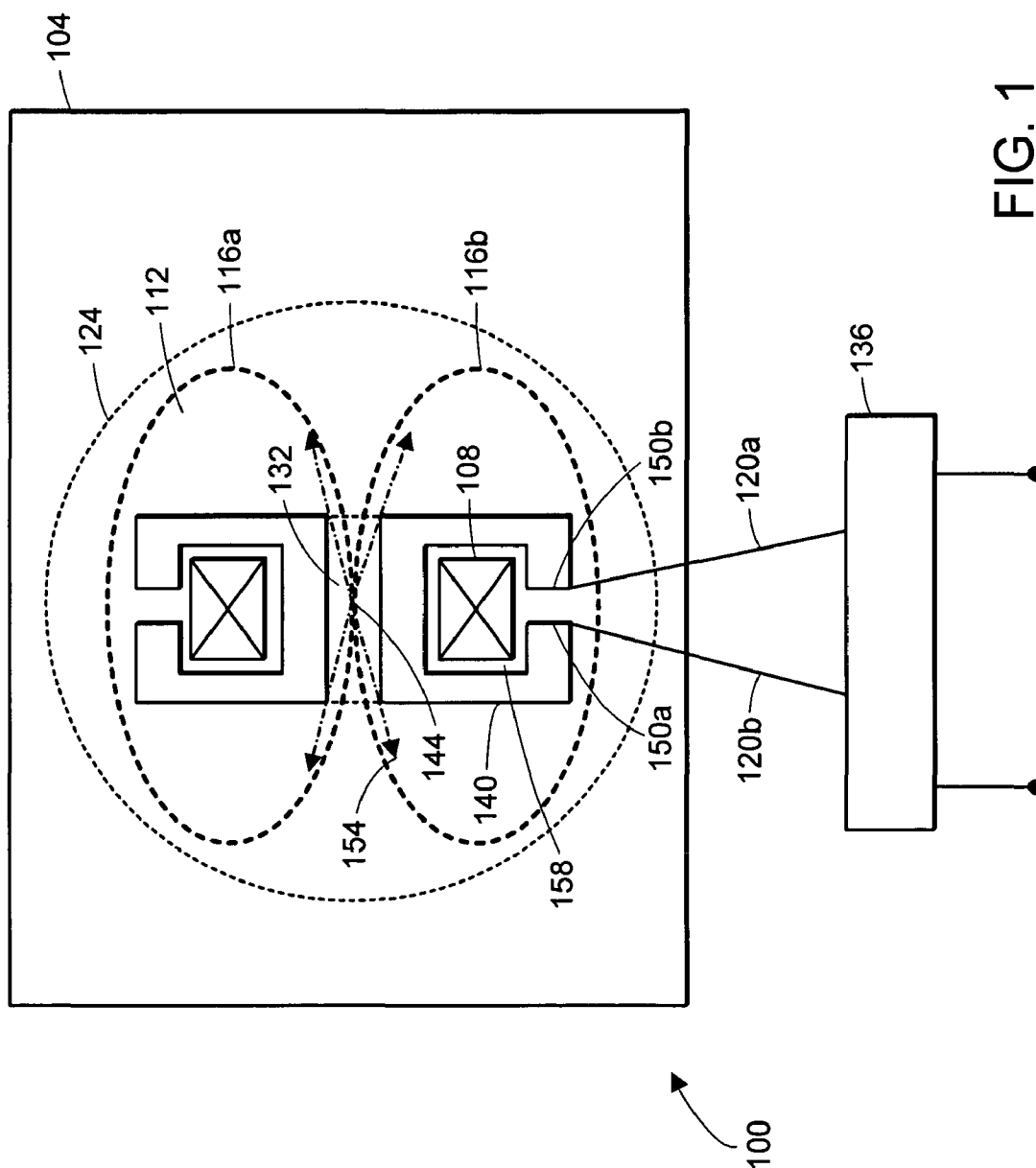
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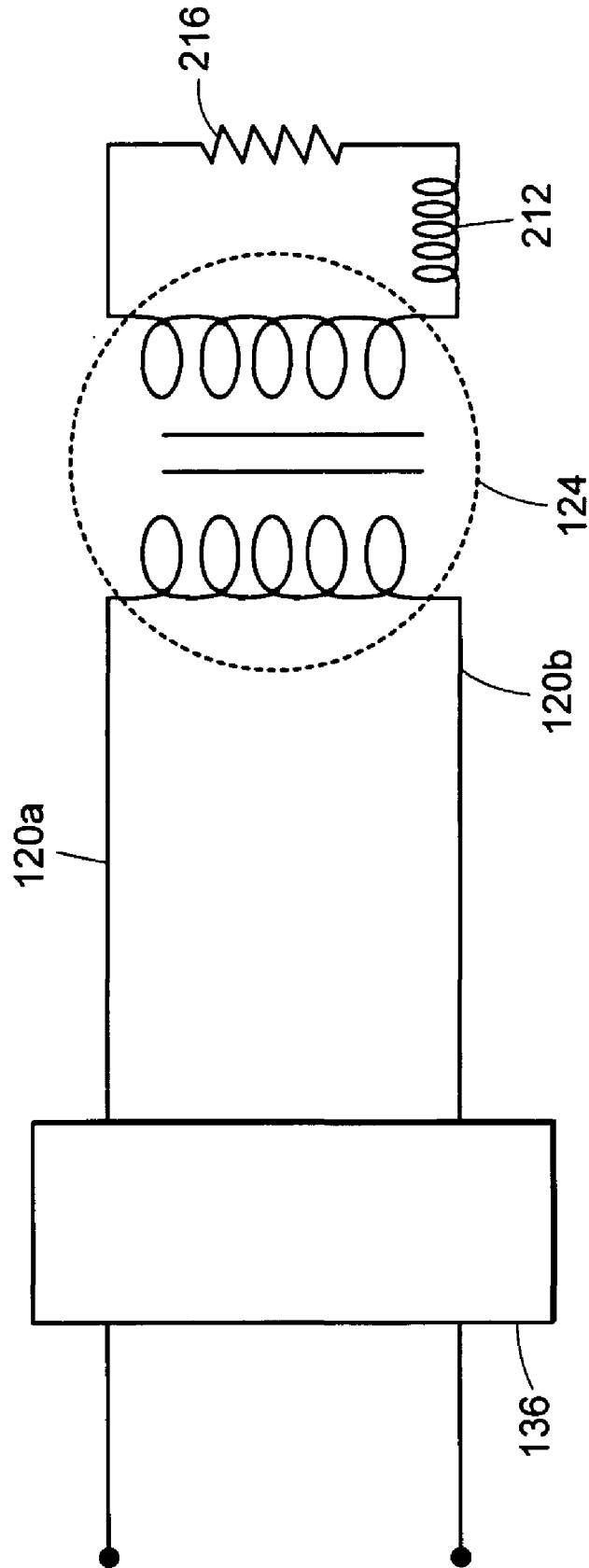
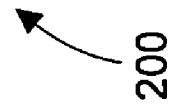


FIG. 2



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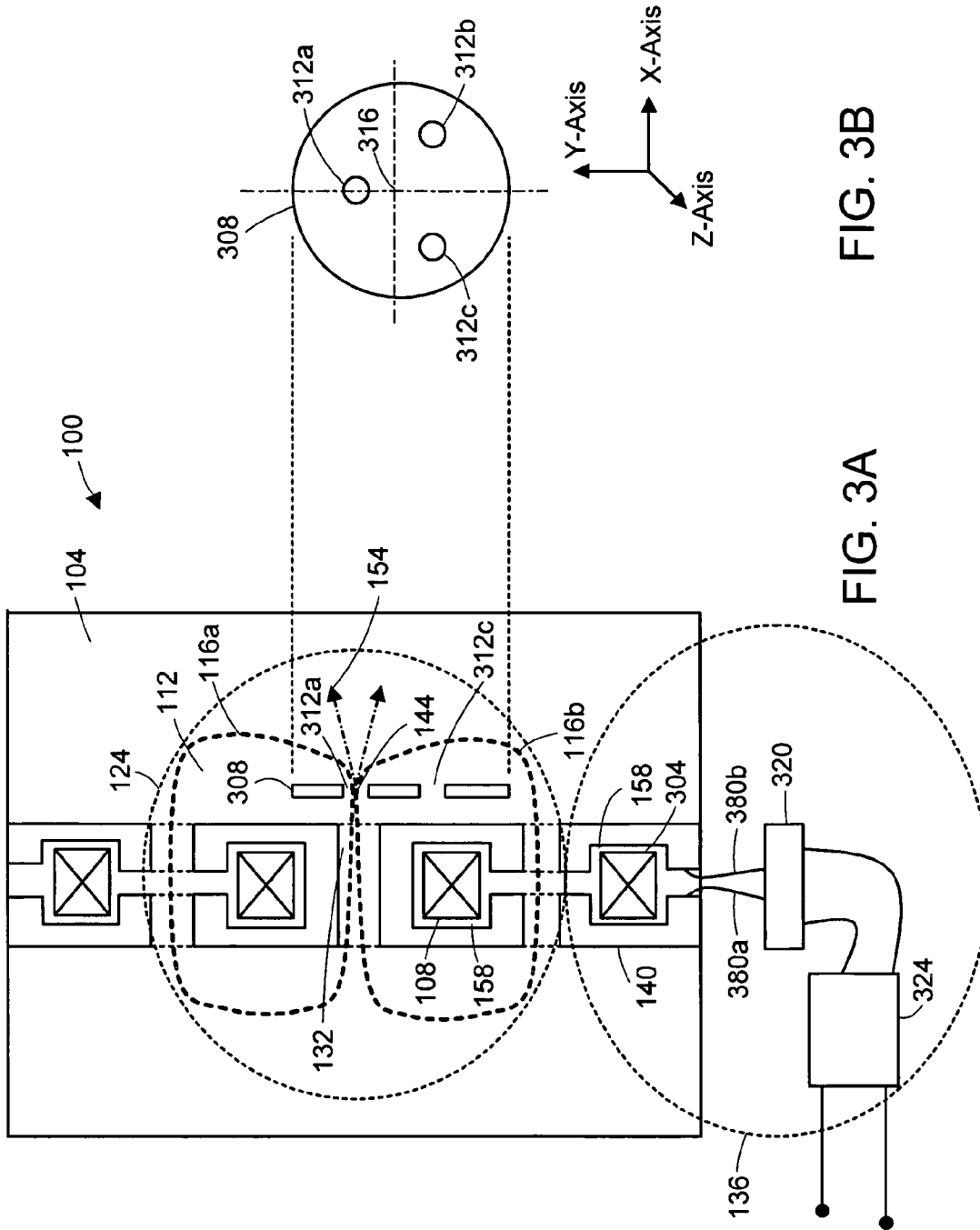


FIG. 3B

FIG. 3A

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